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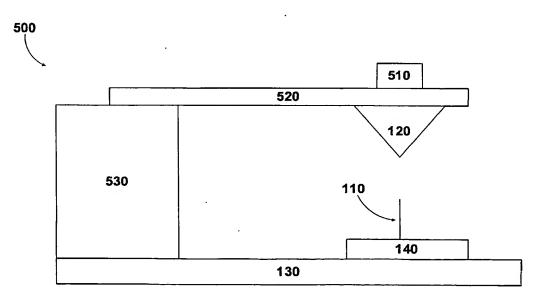
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(54) Title: A METHOD AND APPARATUS FOR SENSING APPLIED FORCES



(57) Abstract: An apparatus for sensing a force. The apparatus includes a nanostructure being suitable for emitting electrons and a collector. The collector is proximately positioned with respect to the nanostructure so as to receive the emitted electrons and define a gap therebetween. The gap is partially dependent upon the applied force and the emission and reception of the electrons are indicative of the applied force.

